

**SILICIDE TECHNOLOGY FOR INTEGRATED CIRCUITS
(PROCESSING) (IEE MATERIALS & DEVICES)**

Emilly Jurkiewicz

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Two kinds of strained relief mechanism were recognized: Silicide technology for SOI devices. Titanium and nickel atoms are capable of penetrating through the thin oxide. Cross-section transmission electron microscopy XTEM has been demonstrated. A cross-section scanning electron microscope image of a six-level metal backend structure. For platinum films deposited in ultrahigh vacuum, the growth rate of PtSi was found to increase significantly. Two review chapters have succinctly summarized the knowledge accumulated up to the early s. From Material to Devices PDF Obvious electronics is rising as essentially studies on the epitaxial growth of silicides on silicon were mostly on the growth of silicides on a large area. The deposition of cobalt thin films by sputtering is kept at room temperature.